

Attorney Docket No. 008401 06



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In re Application of: Kenneth S. Collins, Hiroji Hanawa, Kartik Ramaswamy,
Andrew Nguyen, Amir Al-Bayati, Biagio Gallo, and Gonzalo
Antonio Monroy

Entitled: PLASMA IMMERSION ION IMPLANTATION PROCESS USING AN INDUCTIVELY COUPLED PLASMA SOURCE HAVING LOW DISSOCIATION AND LOW MINIMUM PLASMA VOLTAGE

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Sir:

Enclosed herewith for filing is a patent application entitled PLASMA IMMERSION ION IMPLANTATION PROCESS USING AN INDUCTIVELY COUPLED PLASMA SOURCE HAVING LOW DISSOCIATION AND LOW MINIMUM PLASMA VOLTAGE including 141 pages of specification, 85 claims and abstract, and 85 sheets of drawings (Figures 1-112).

This application is being filed missing parts and specifically without a declaration by the inventors and without a filing fee. The application is being filed in the names of the inventors, Kenneth S. Collins, Hiroji Hanawa, Kartik Ramaswamy, Andrew Nguyen, Amir Al-Bayati, Biagio Gallo, and Gonzalo Antonio Monroy.

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Dated: August 22, 2003

Respectfully submitted,

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